

Tool Name: ICPRIE Diamond

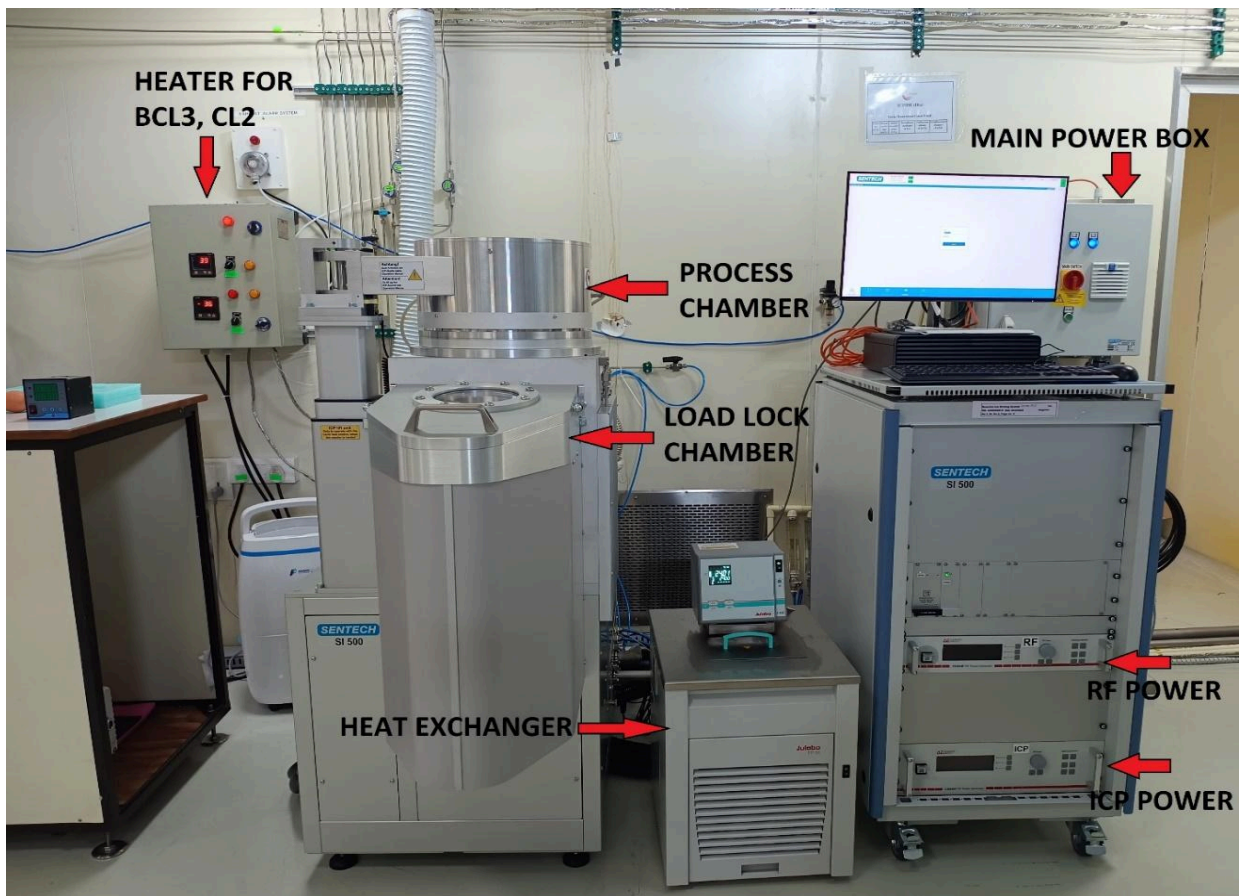
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Front View

Location: - Nanoelectronics Processing Lab (NanoE bldg, 1st floor)

Specifications:-

1. Maximum Process time should be 20 minutes.
2. One can execute 10 min cycles with a 10 min gap.
3. Maximum RF supply = 600 W
4. Maximum ICP supply = 2500 W
5. Maximum allowed process gas flow = CL2 - 172 sccm, BCL3 - 82 sccm, CHF3 - 100sccm, O2 - 99sccm, N2 - 100sccm, CF4 - 84sccm, Ar - 145sccm, SF6 - 130sccm.
6. Water flow requirement = 6 lpm for main system, 6 lpm for control rack
7. Heat Exchanger = Max Temperature 40°C (Heat exchanger temperature should always be 10°C lower than the process temperature)
8. Before running any process in the chamber following recipes has to be done
 - O2 cleaning 10 minutes - For Chamber cleaning
 - Chamber conditioning - Actual process to be done to condition the chamber for actual run